



Eisenhower Fellowships Association of Sri Lanka

“Leaders bettering the world around them”

PRESS RELEASE

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US-Based Eisenhower Fellowships Calls for Applications from Sri Lanka

Established in honor of former US President Dwight Eisenhower in 1953, the prestigious Eisenhower Fellowship is a unique, individualized seven week fellowship programme aimed at developing a network of outstanding leaders and change agents from across the world. Sri Lanka has been among the limited number of countries that has consistently been represented in the programme since its inception.

Past Sri Lankan Eisenhower Fellows are among the most influential voices in the country, and span a wide array of fields including law, politics, banking, technology, urban development, the arts, environment, and medicine.

The selection process for the 2020 Eisenhower Fellowship has now commenced. Applications are currently being sought from persons focused on high impact areas relevant to Sri Lanka including investigative journalism, urban development, police investigation, democratic governance and policy advocacy, the judiciary, education, and environment, among others.

“Acceptance into the Eisenhower Fellowship programme is highly competitive. Therefore we are seeking persons who have made outstanding, relevant and timely contributions to the country in their respective fields, and have the potential to have significant impact in Sri Lanka on their return” said J C Weliamuna, Chairman of the Eisenhower Fellowships Association of Sri Lanka. “Our intention is to provide development opportunities and a supportive local and international network for the next generation of Sri Lankan leaders” he added.

All candidates must submit an online application by May 15, 2019 and follow a common selection process. Interested candidates are encouraged to refer to www.efworld.org for more information on the fellowship programme and reach out to the Eisenhower Fellowships Association of Sri Lanka at EisenhowerFoundationsl@gmail.com for further details and guidance on the application process.